



## Extreme Ultraviolet and X-ray Optics for Plasma Diagnostics: Systems and Technologies

Guest Editors:

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### Message from the Guest Editors

Extreme ultraviolet (EUV) and soft X-rays are important information carriers for laser-driven, heavy-ion-driven, Z-pinch, and other inertial confinement fusion and magnetic-confinement fusion experiments. This Special Issue plans to provide an overview of recent advances in high-performance extreme ultraviolet and soft X-ray optical systems and their applications in different fields.

This Special Issue focuses on the new structural design, device development and exploration of new diagnostic methods, technologies and systems for EUV and soft X-ray optics for plasma diagnostics. Potential topics include, but are not limited to:

- EUV and soft X-ray imaging system;
- EUV and soft X-ray spectroscopy element and system;
- High time-resolved EUV and soft X-ray measurement device;
- EUV and soft X-ray diagnostic techniques in inertial confinement fusion;
- EUV and soft X-ray diagnostic techniques in magnetic confinement fusion;
- Key EUV and soft X-ray optical elements for plasma diagnostics;
- Novel optical structures for EUV and soft X-ray imaging or spectroscopy;
- Key technologies in EUV and soft X-ray optics development.

